

**ION MILL PROCESS WITH SACRIFICIAL MASK LAYER TO FABRICATE
POLE TIP FOR PERPENDICULAR RECORDING**

FIRST NAMED INVENTOR: QUANG LE

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Atty. ref.:60717-341701

THIS CORRESPONDENCE CHART IS FOR EASE OF UNDERSTANDING
AND INFORMATIONAL PURPOSES ONLY, AND DOES NOT FORM A PART OF
THE FORMAL PATENT APPLICATION.

15	20	slider
	22	ABS
	24	disk
	26	hard layer
	28	soft layer
20	30	perpendicular head
	32	write head
	34	first pole P1
	36	insulation layer
	38	induction coil structure
25	40	coils
	42	insulation layer
	44	P2 shaping layer
	46	magnetic back gap
	48	alumina fill
30	50	P3 probe layer
	52	P3 pole tip
	54	alumina layer
	60	CMP stop layer
	62	seed layer
35	64	photo-resist
	66	cavity
	68	PS sacrificial layer
	70	IM mask
	72	secondary mask
40	74	encapsulating material layer